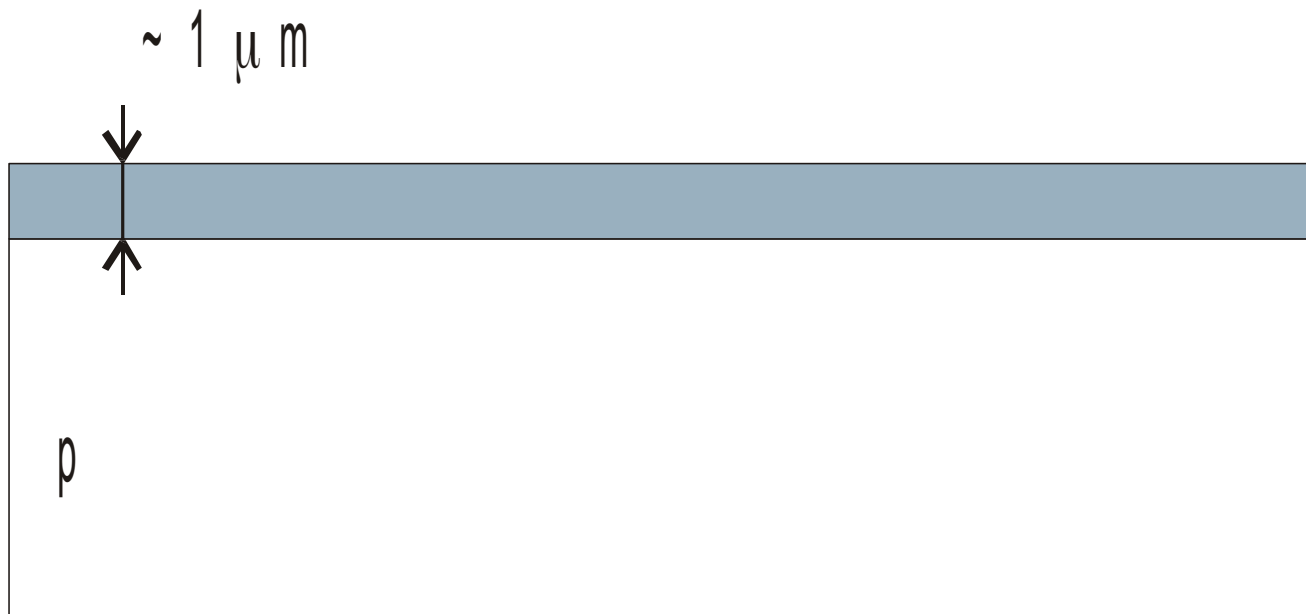
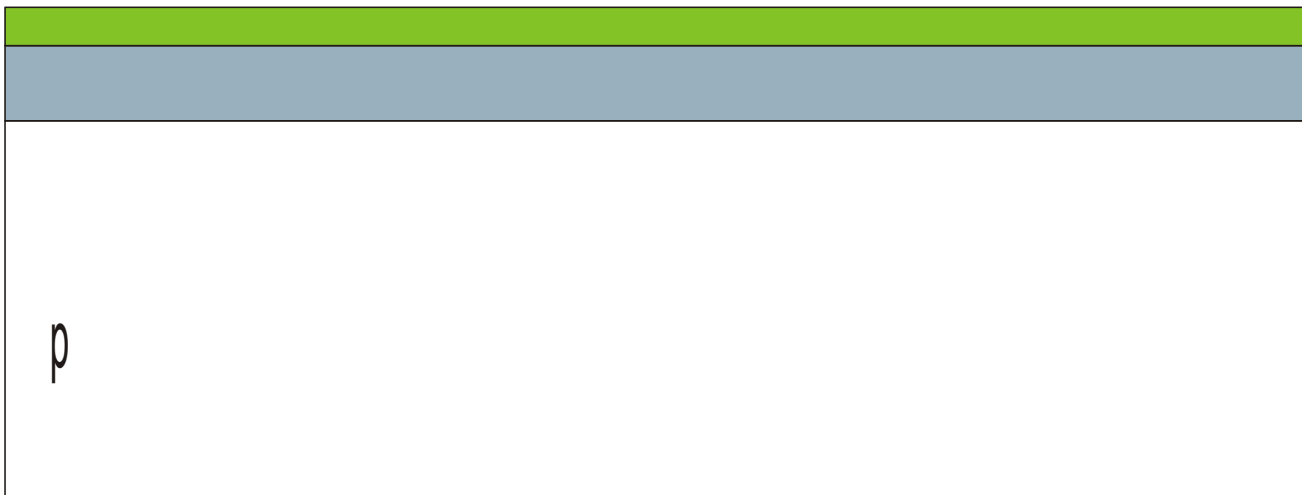


# Manufacturing of NMOS Transistor

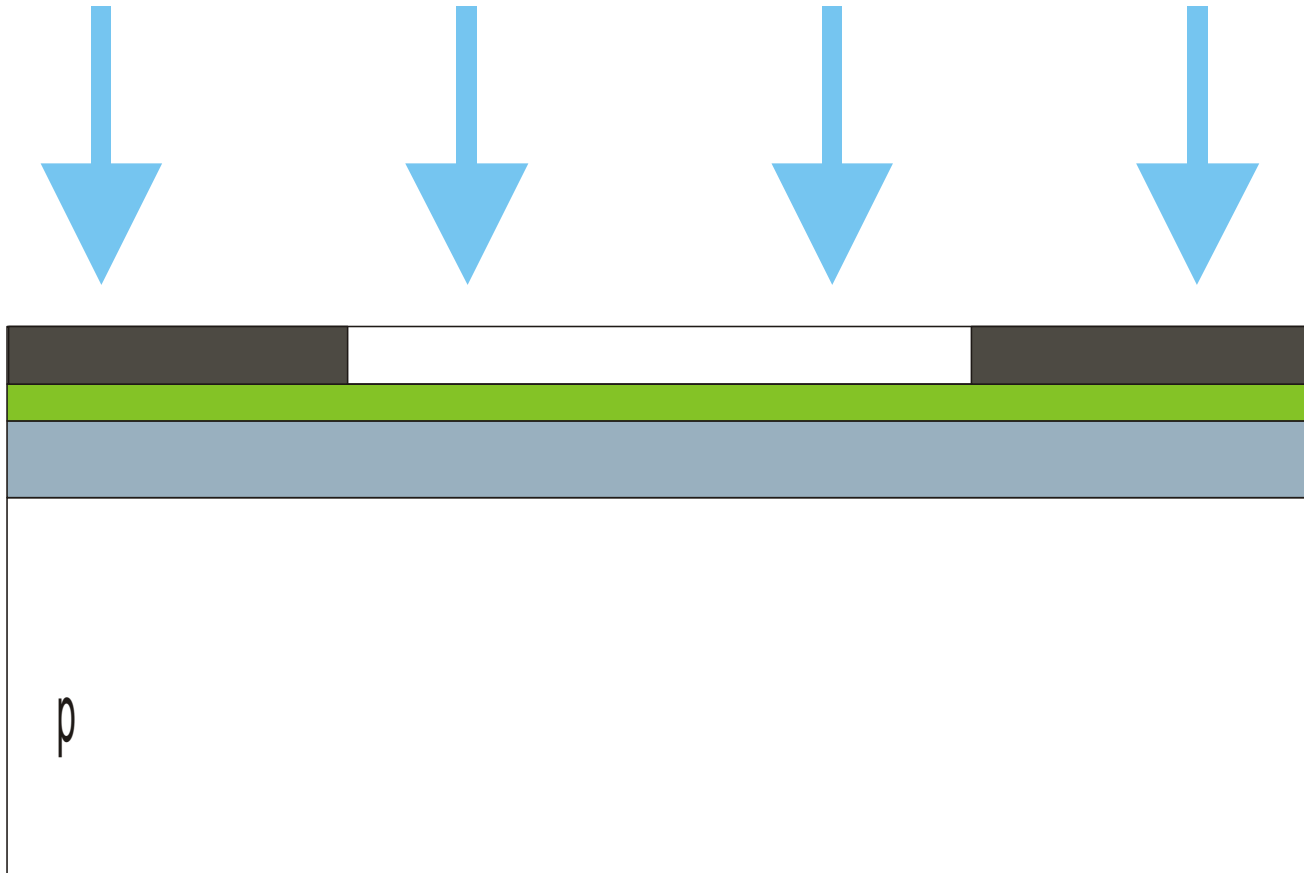
# Substrate Oxidation



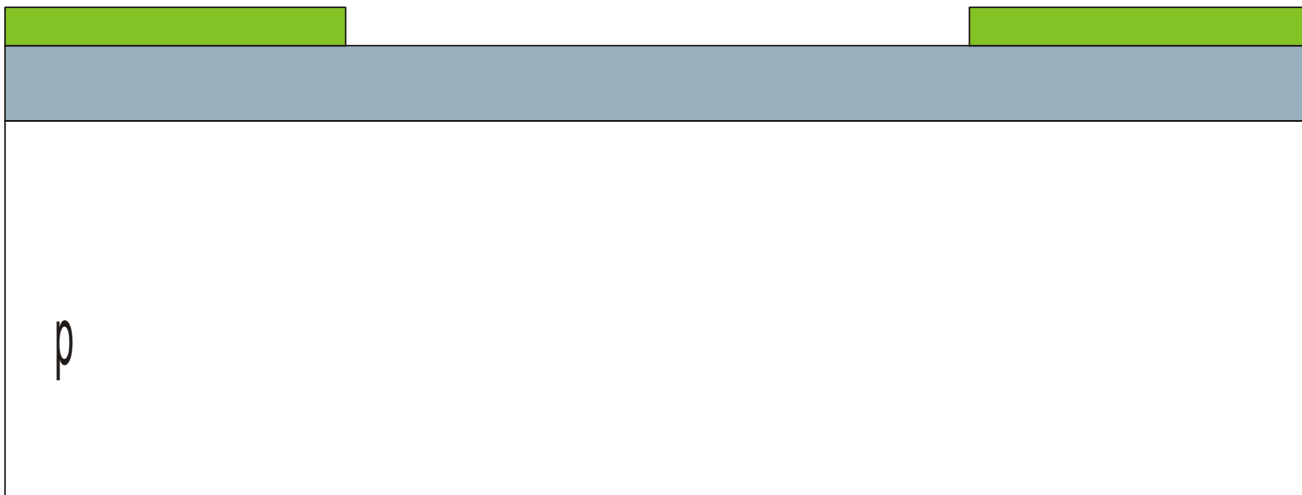
# Deposition of Photoresist



# Mask 1



# Developing of Photoresist



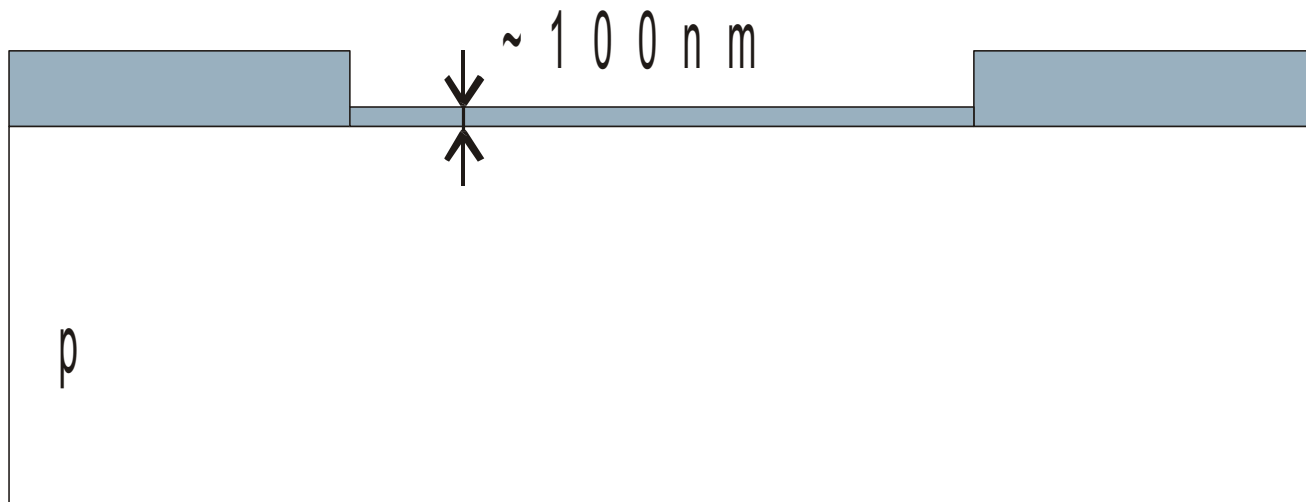
# Oxide Etch



# Removal of Photoresist



# Deposition of Thin Oxide

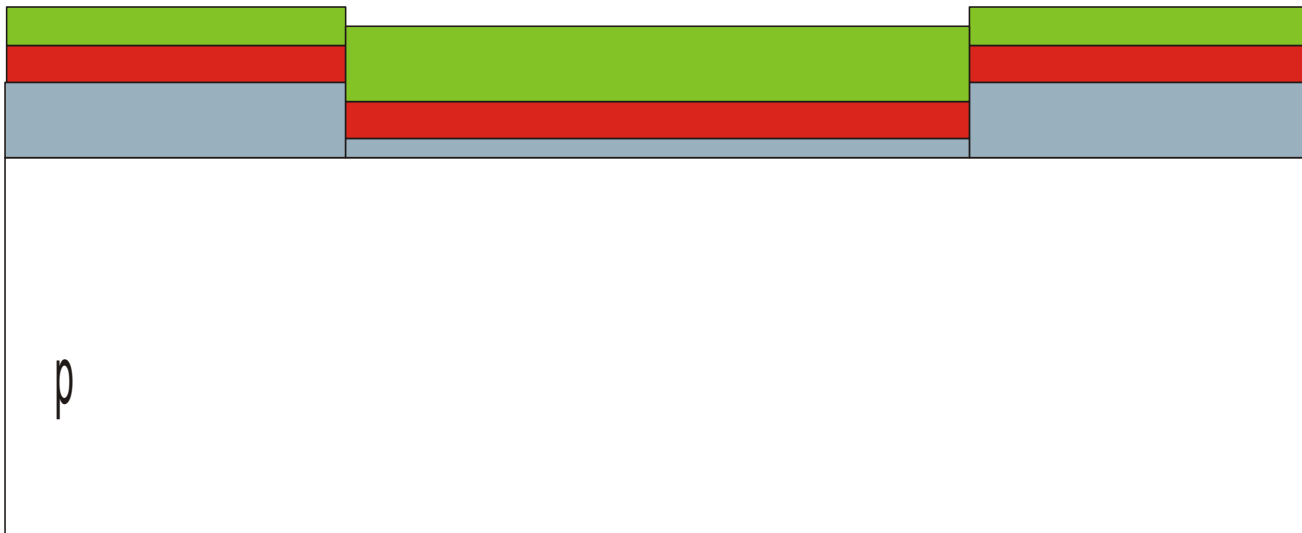




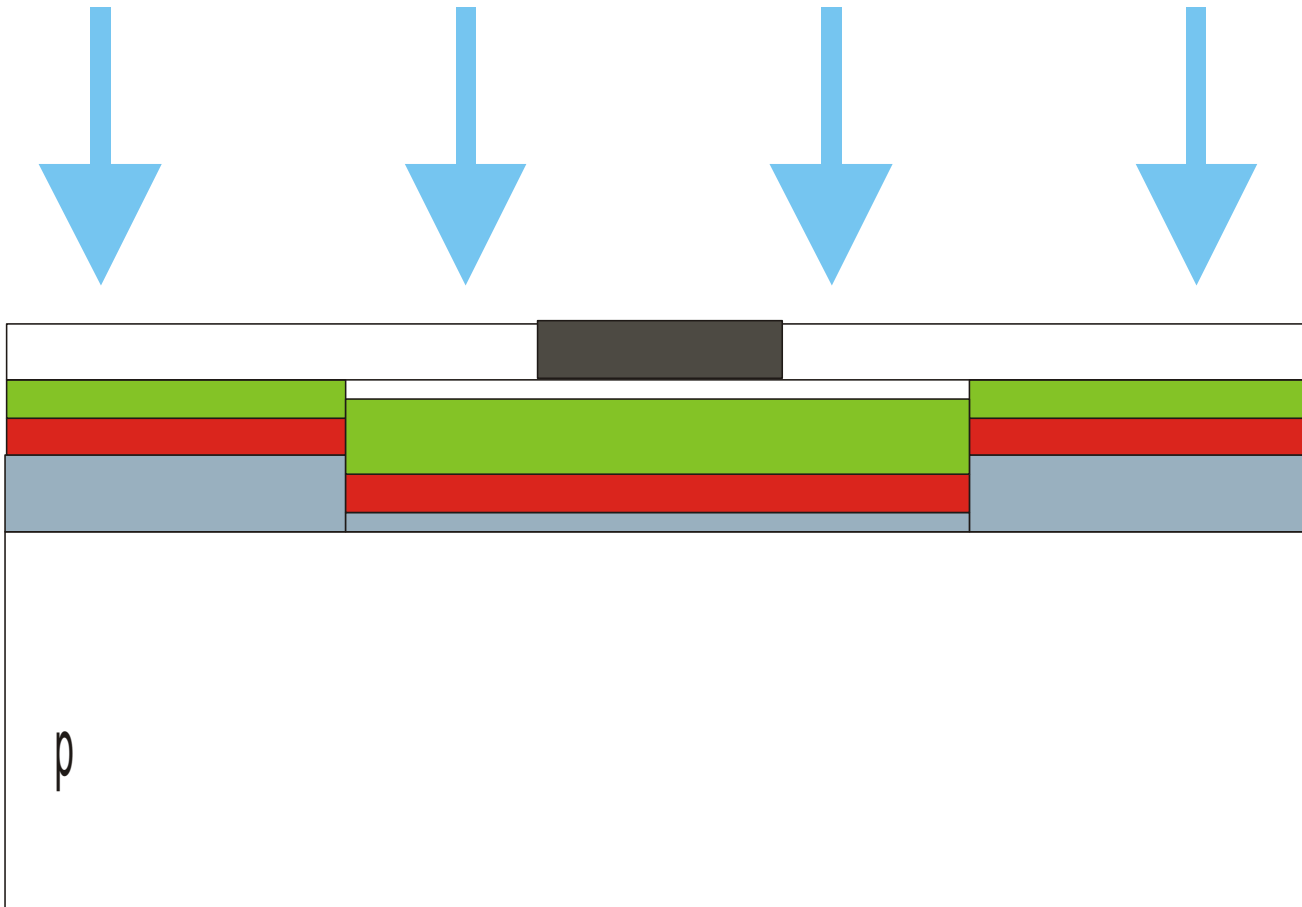
# Deposition of Polysilicon



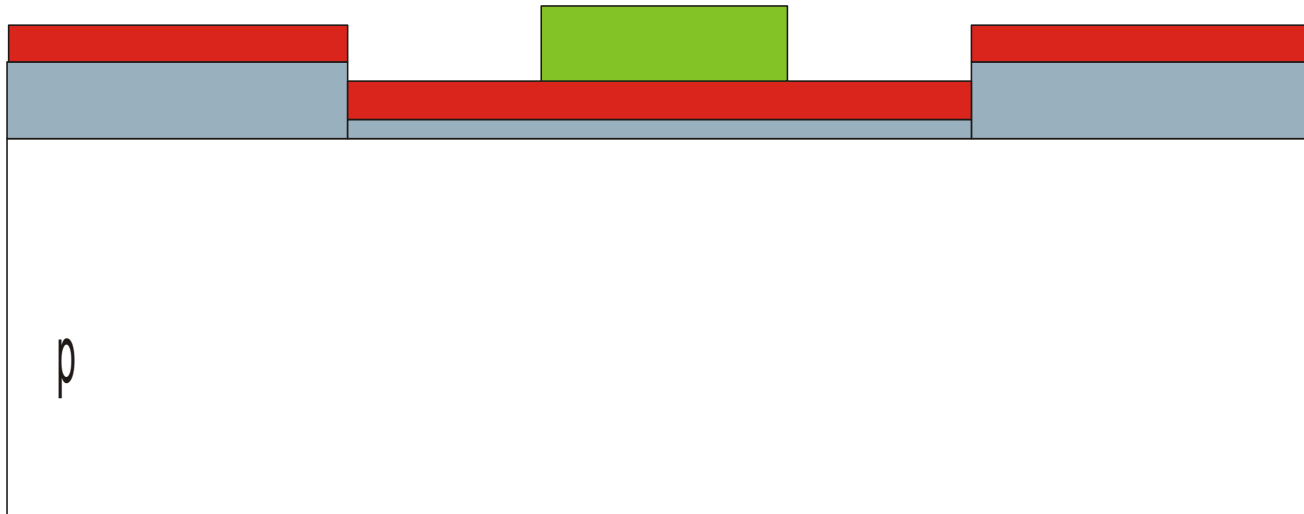
# Deposition of Photoresist



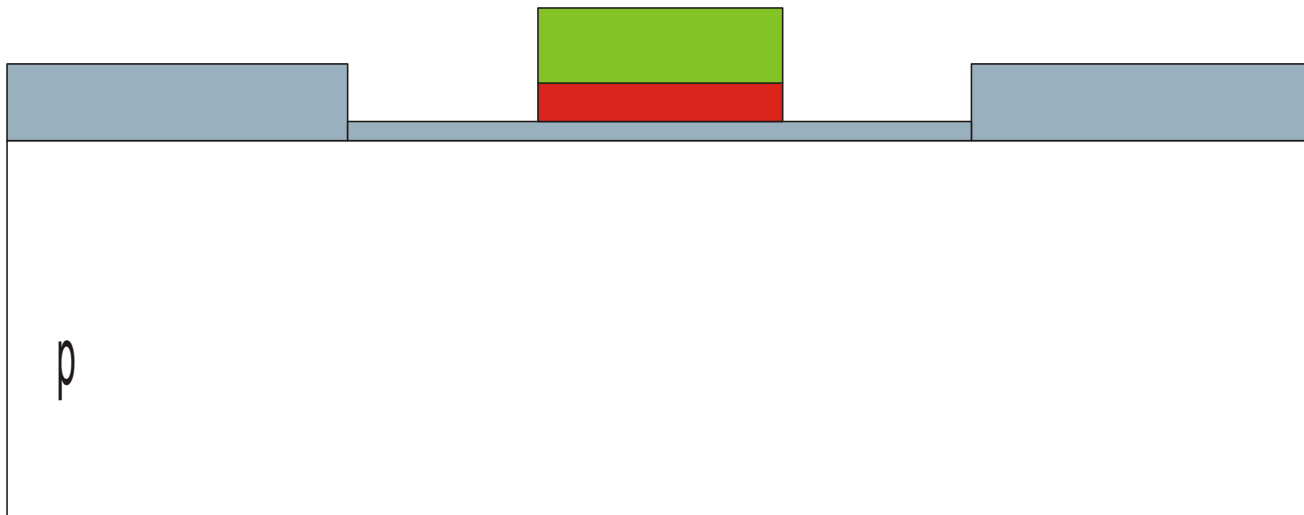
# Mask 2



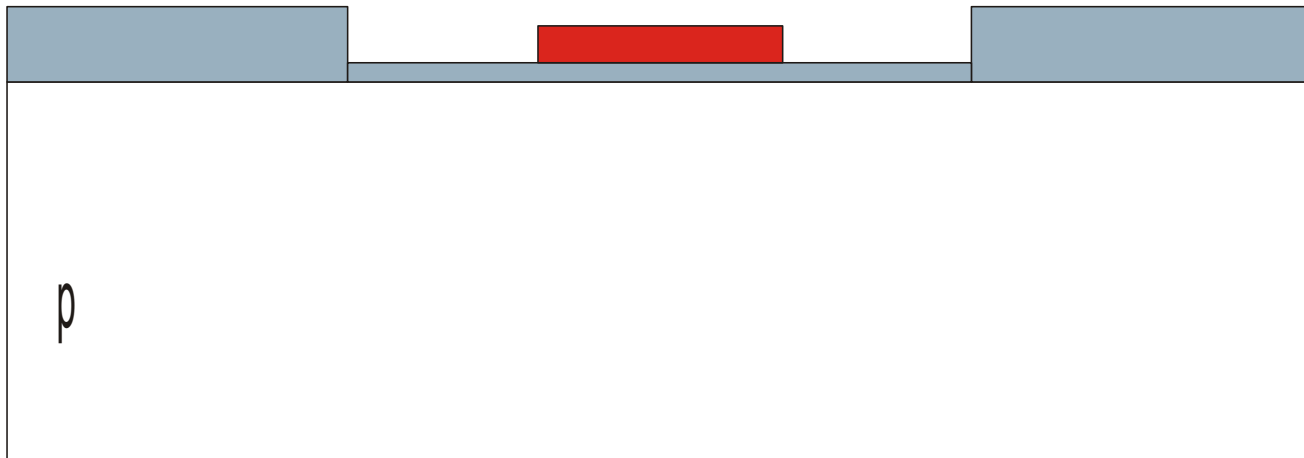
# Developing of Photoresist



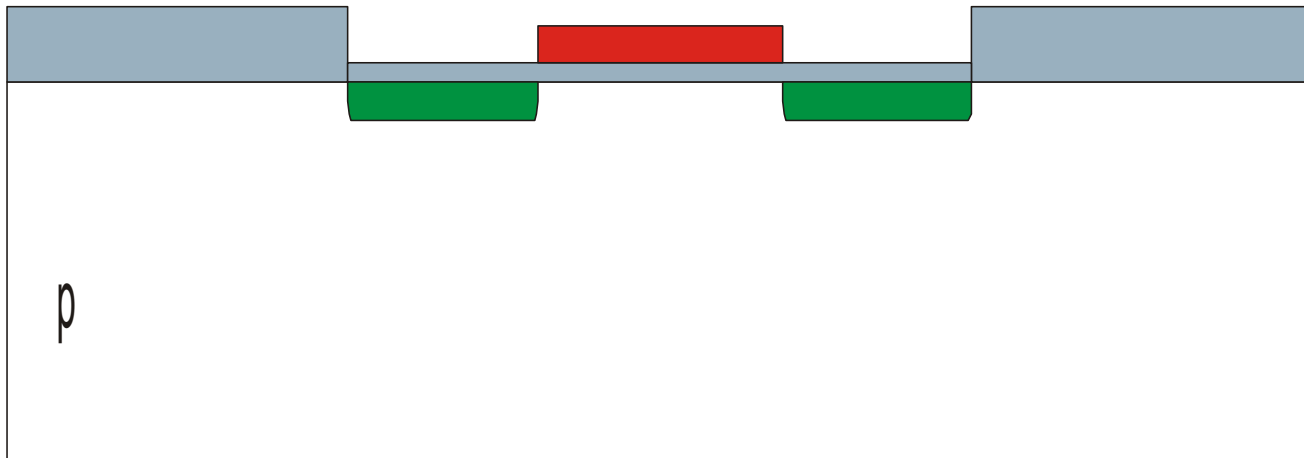
# Polysilicon Etch



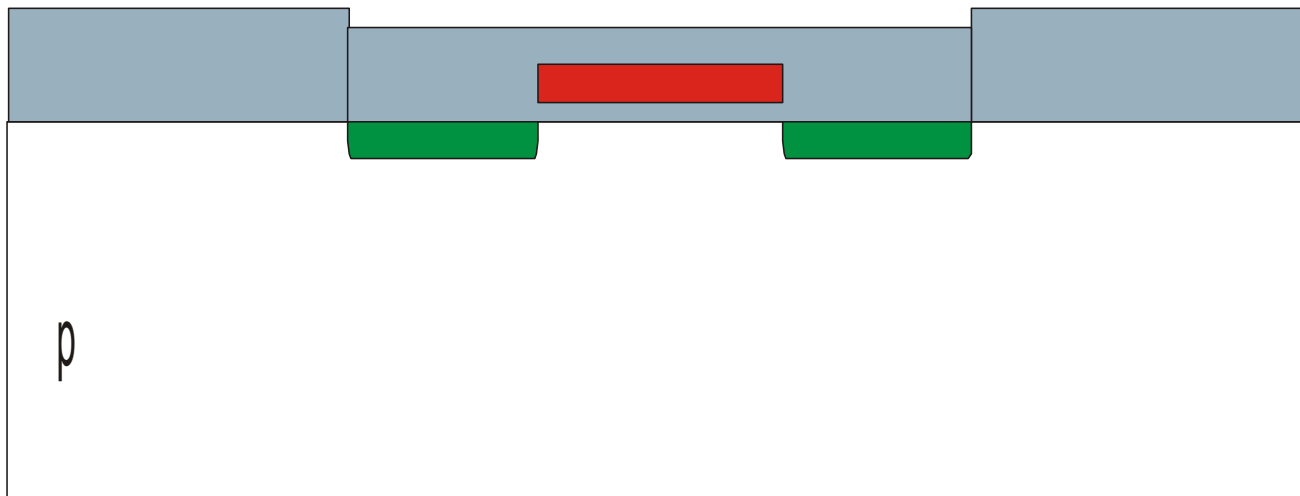
# Removal of Photoresist



# Drain and Source Implantation

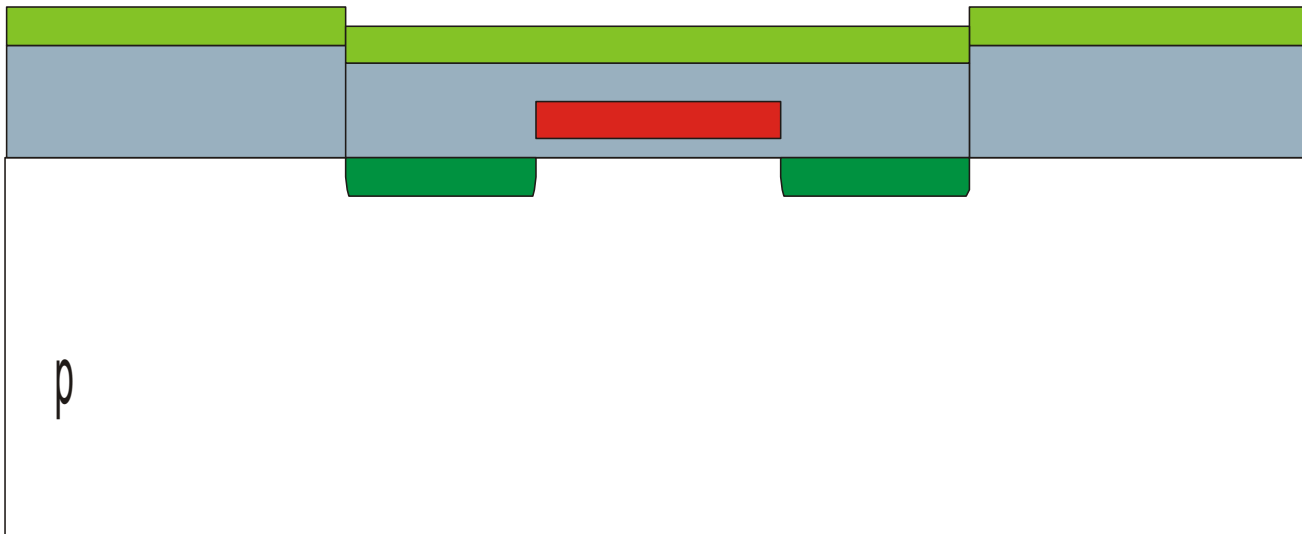


# Deposition of Insulating Layer

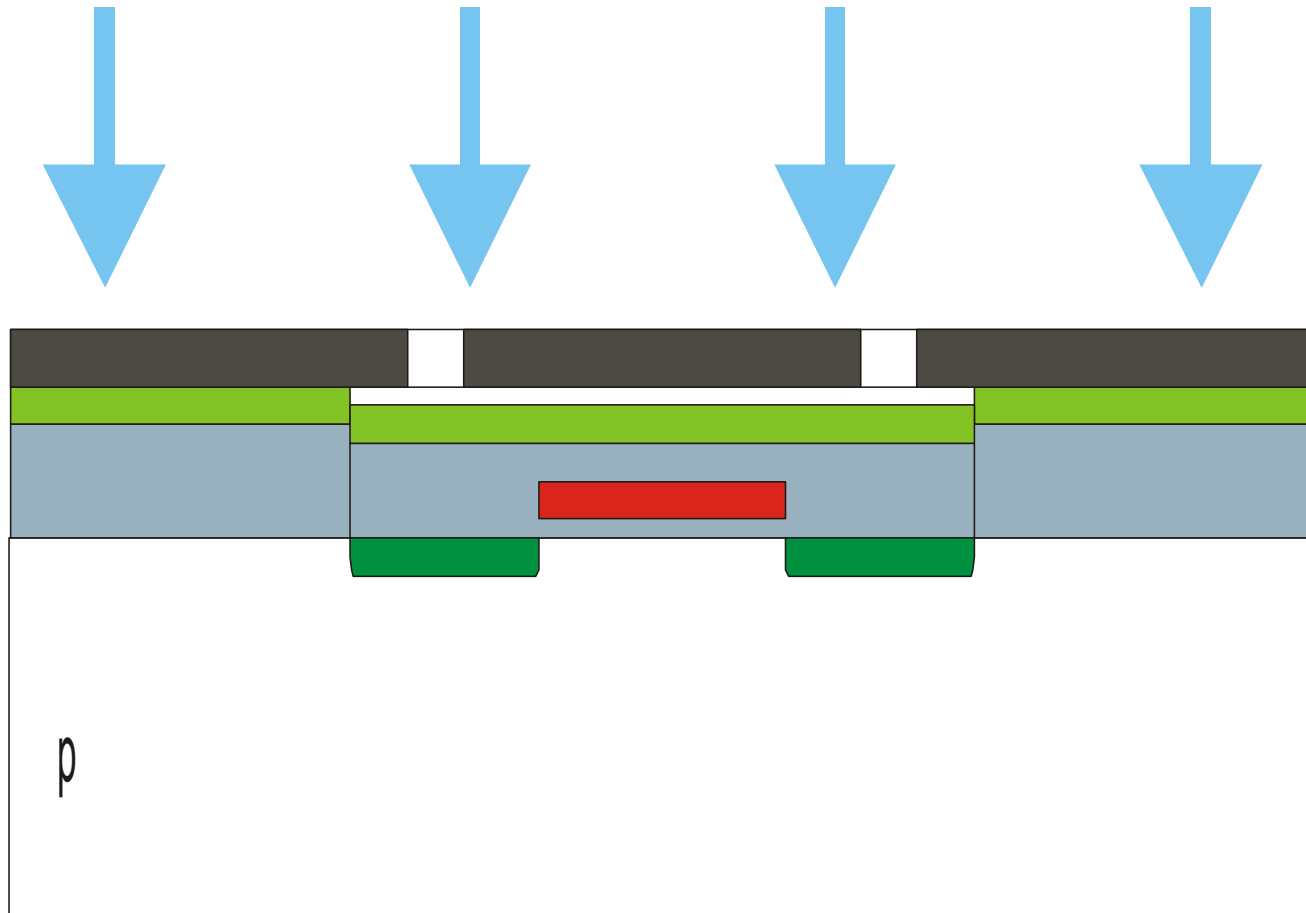




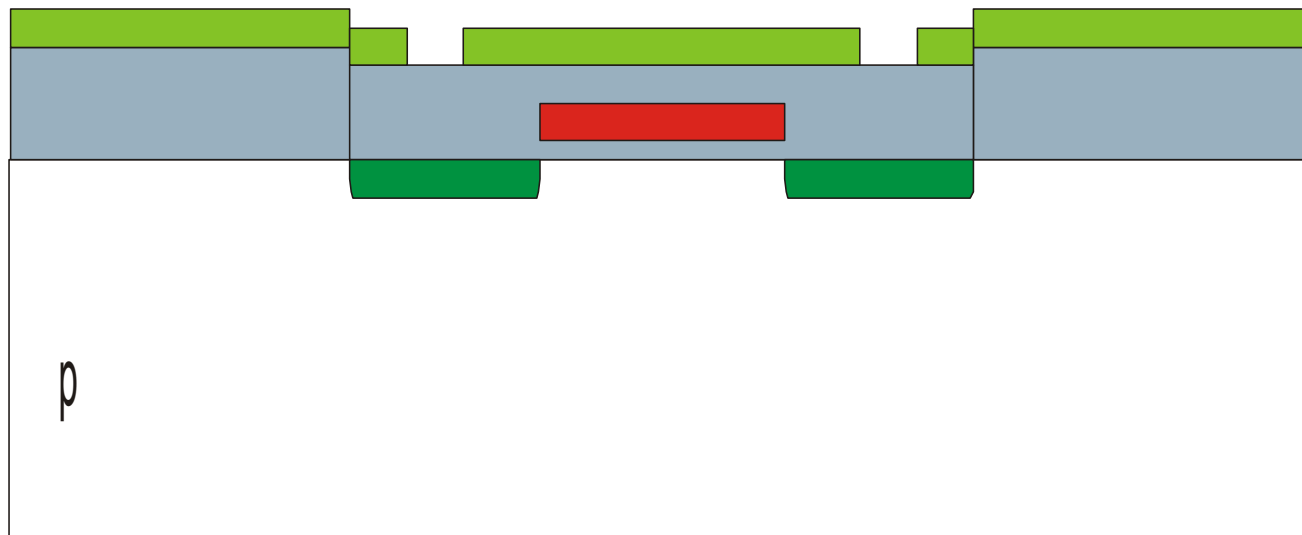
# Deposition of Photoresist



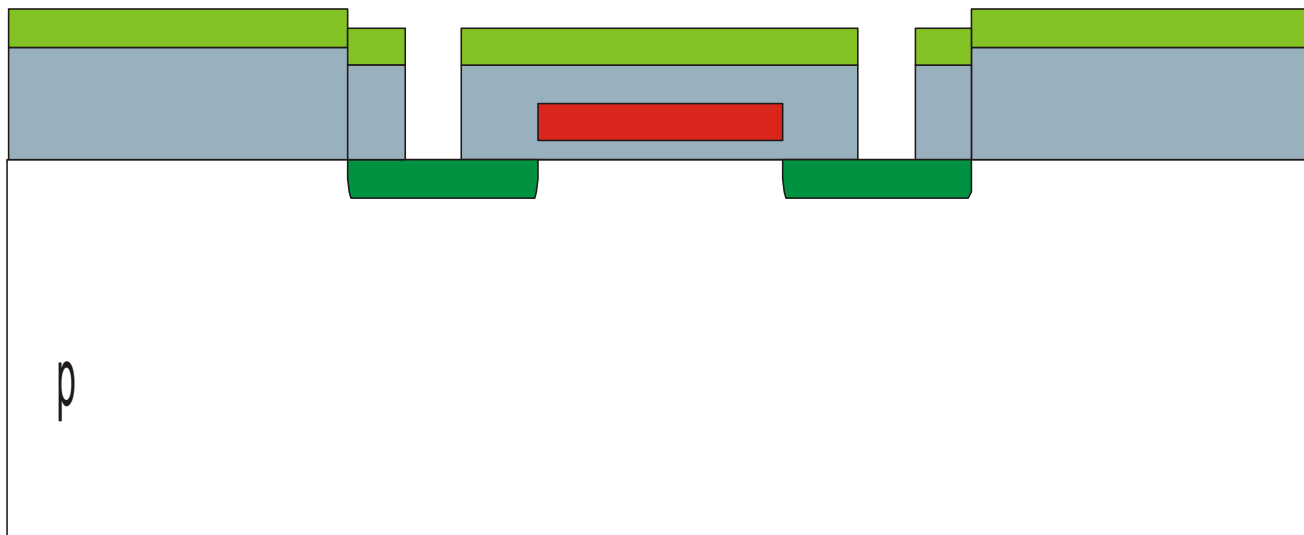
# Mask 3



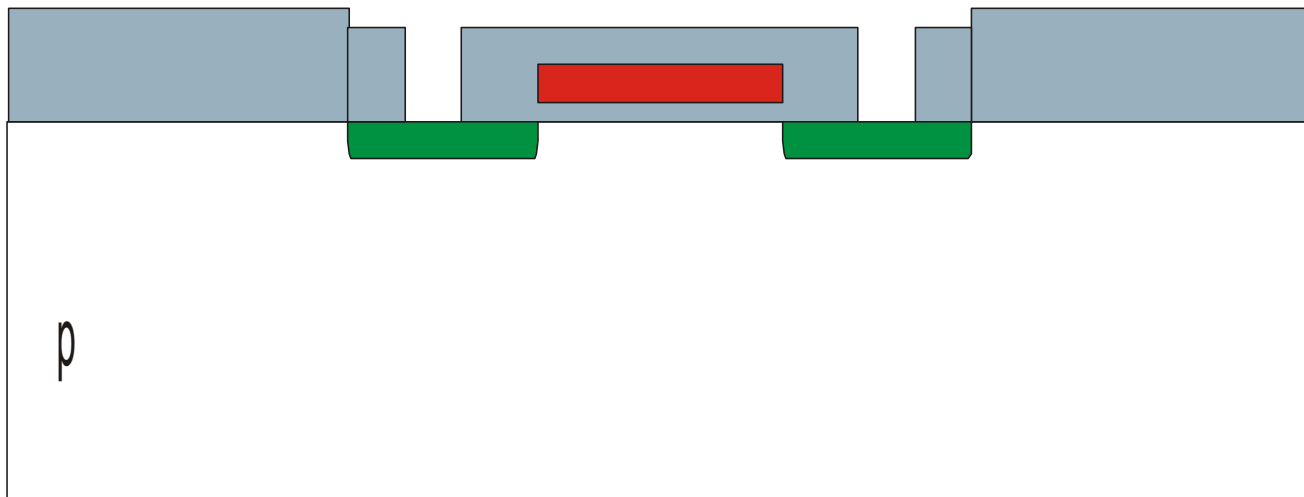
# Developing of Photoresist



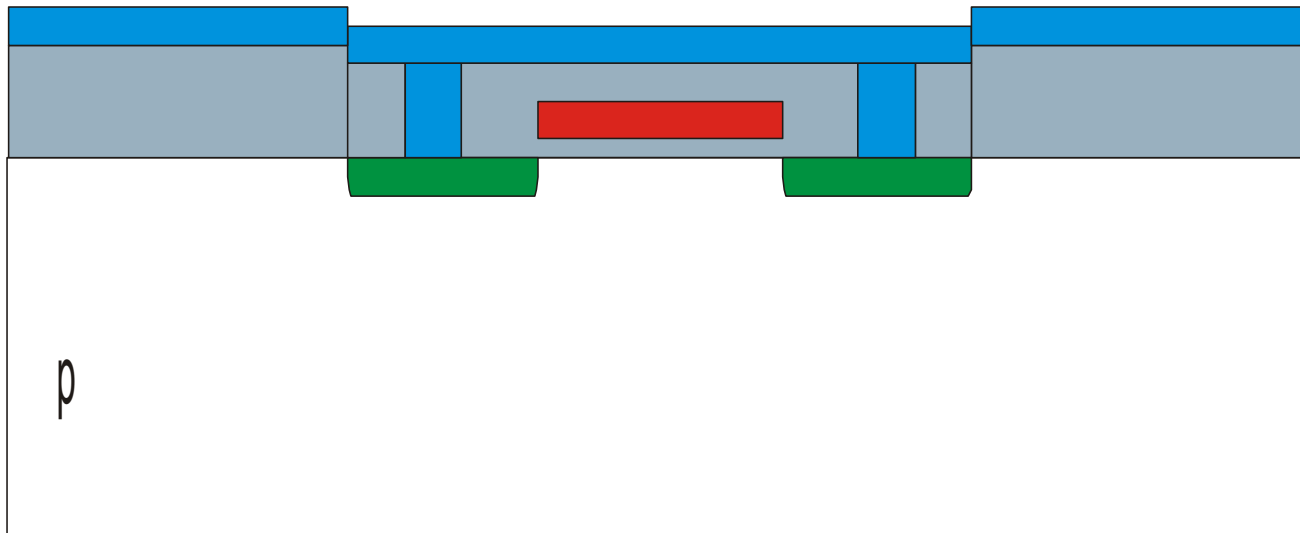
# Oxide Etch



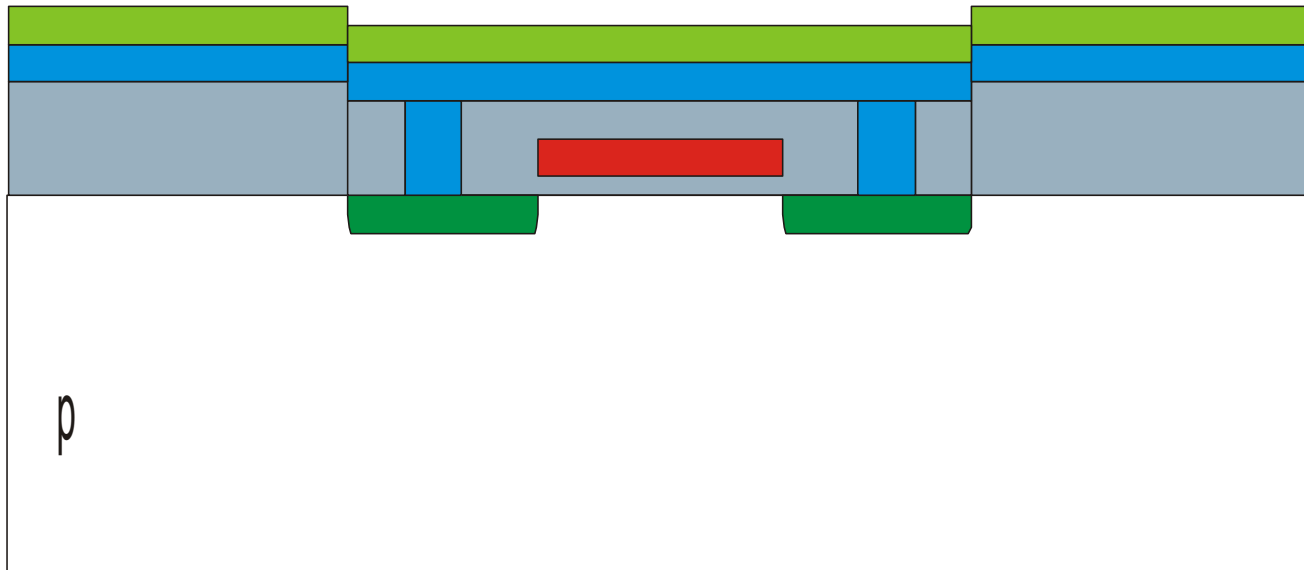
# Removal of Photoresist



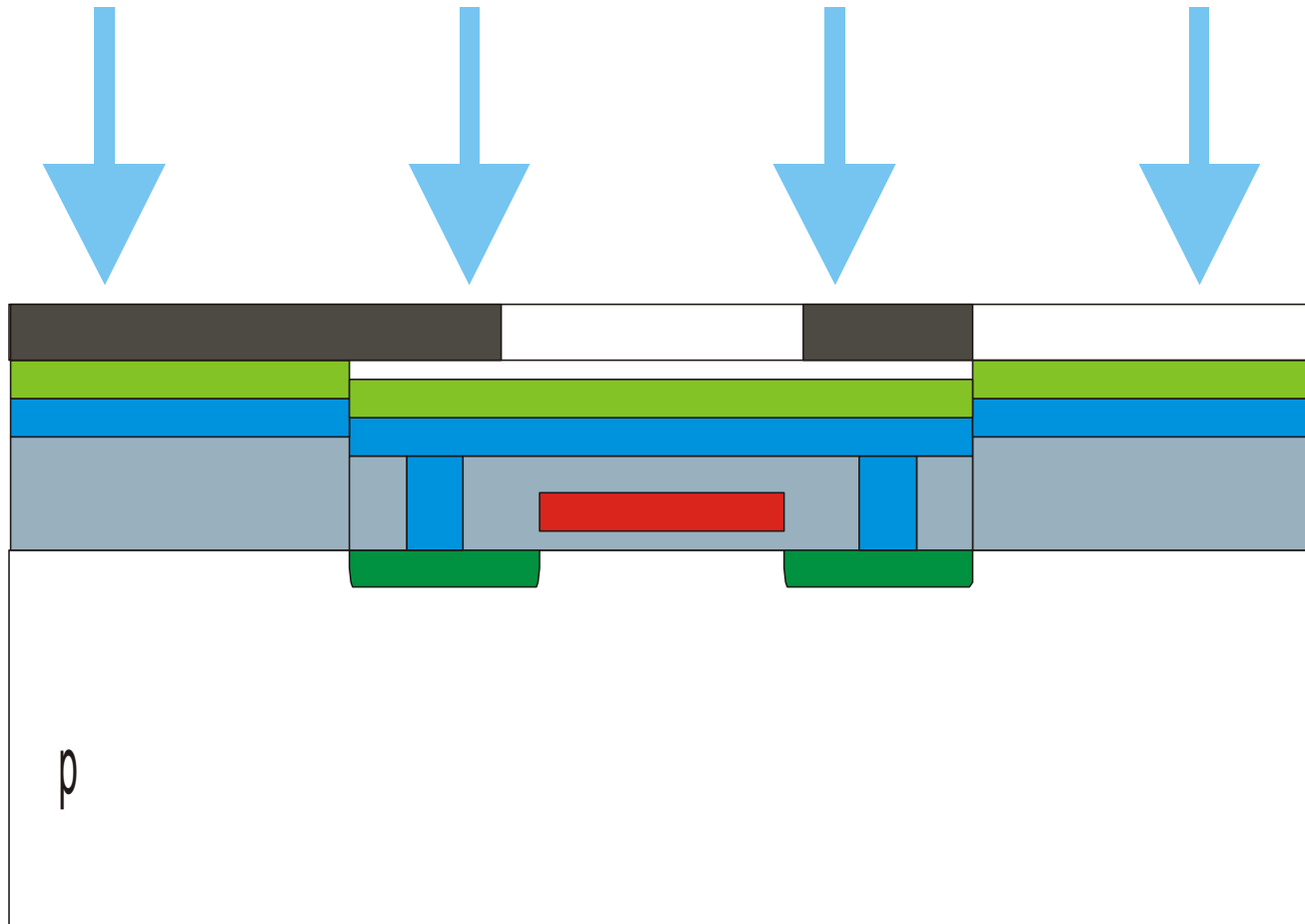
# Metal Deposition



# Photoresist Deposition

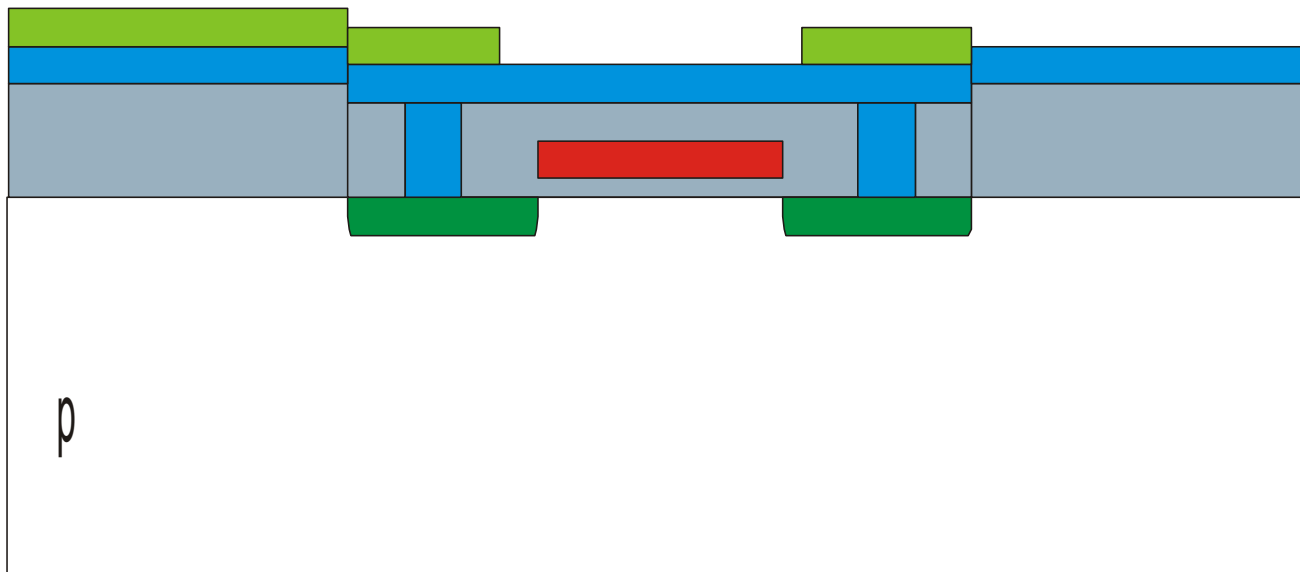


# Mask 4

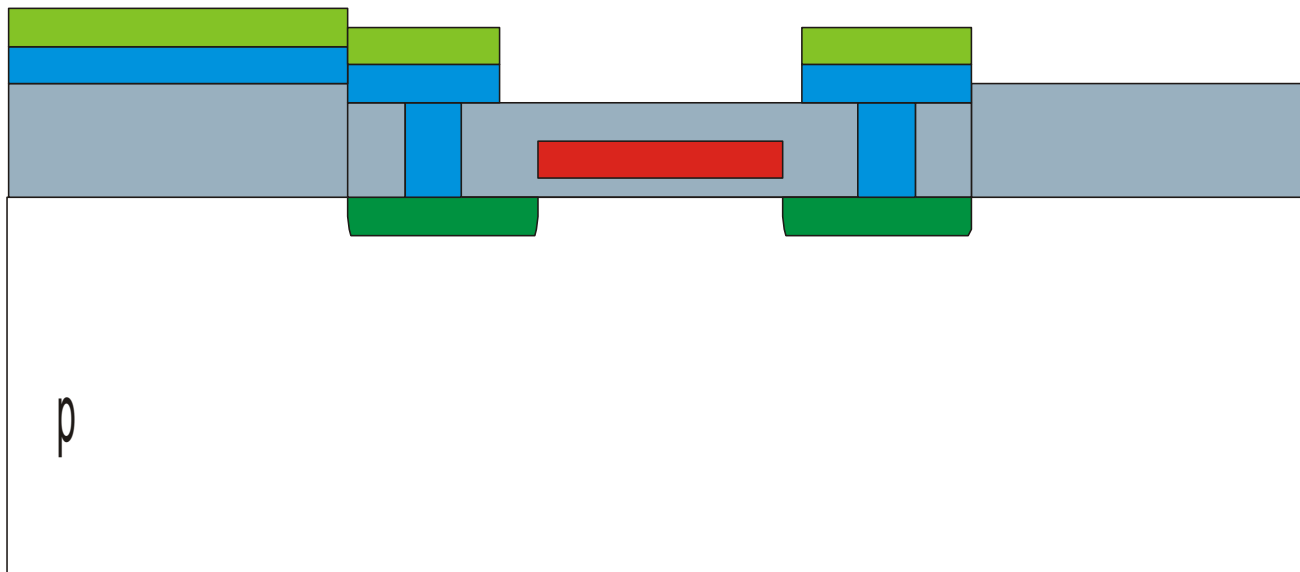




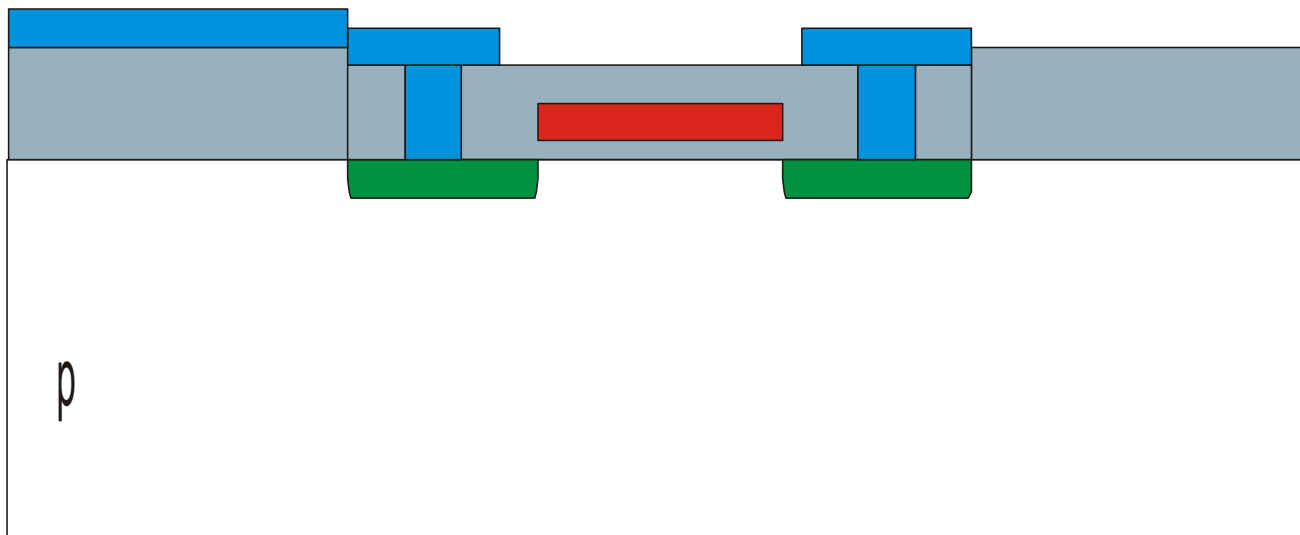
# Developing of Photoresist



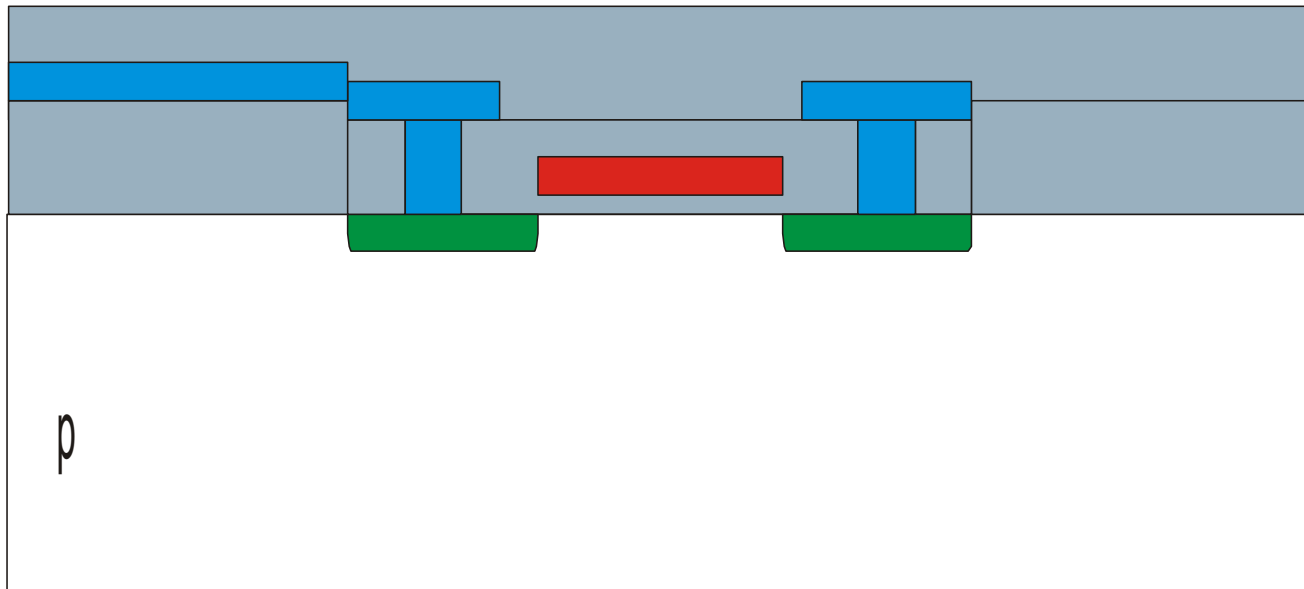
# Metallization Etch



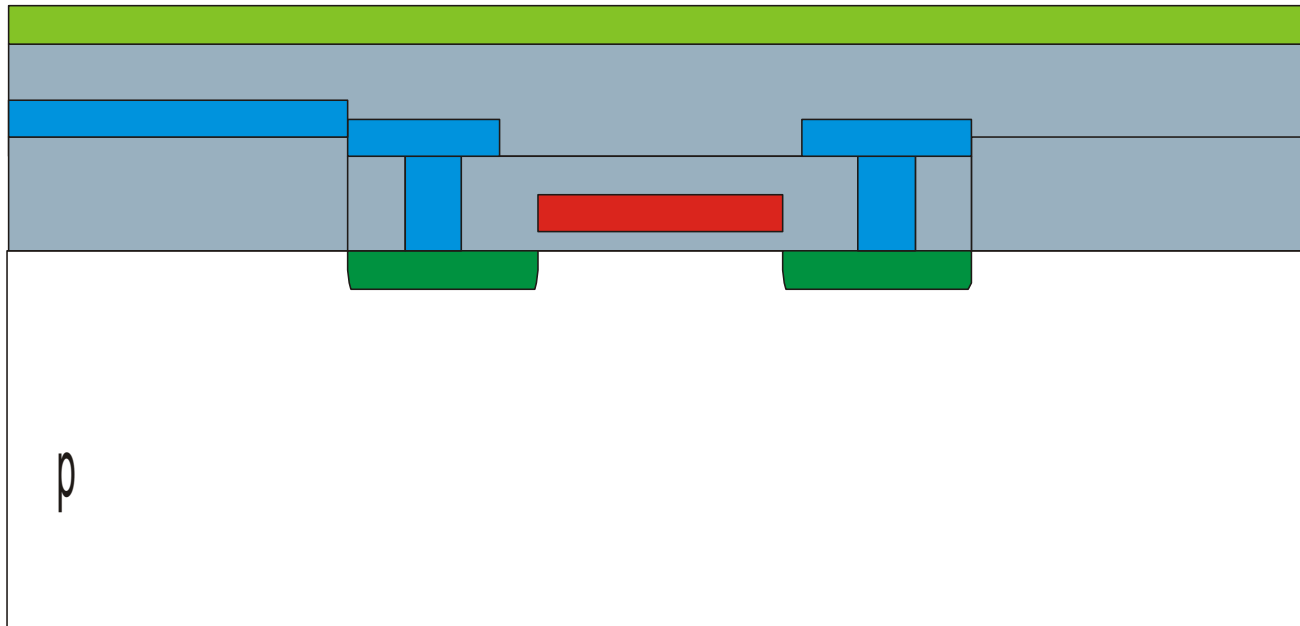
# Removal of Photoresist



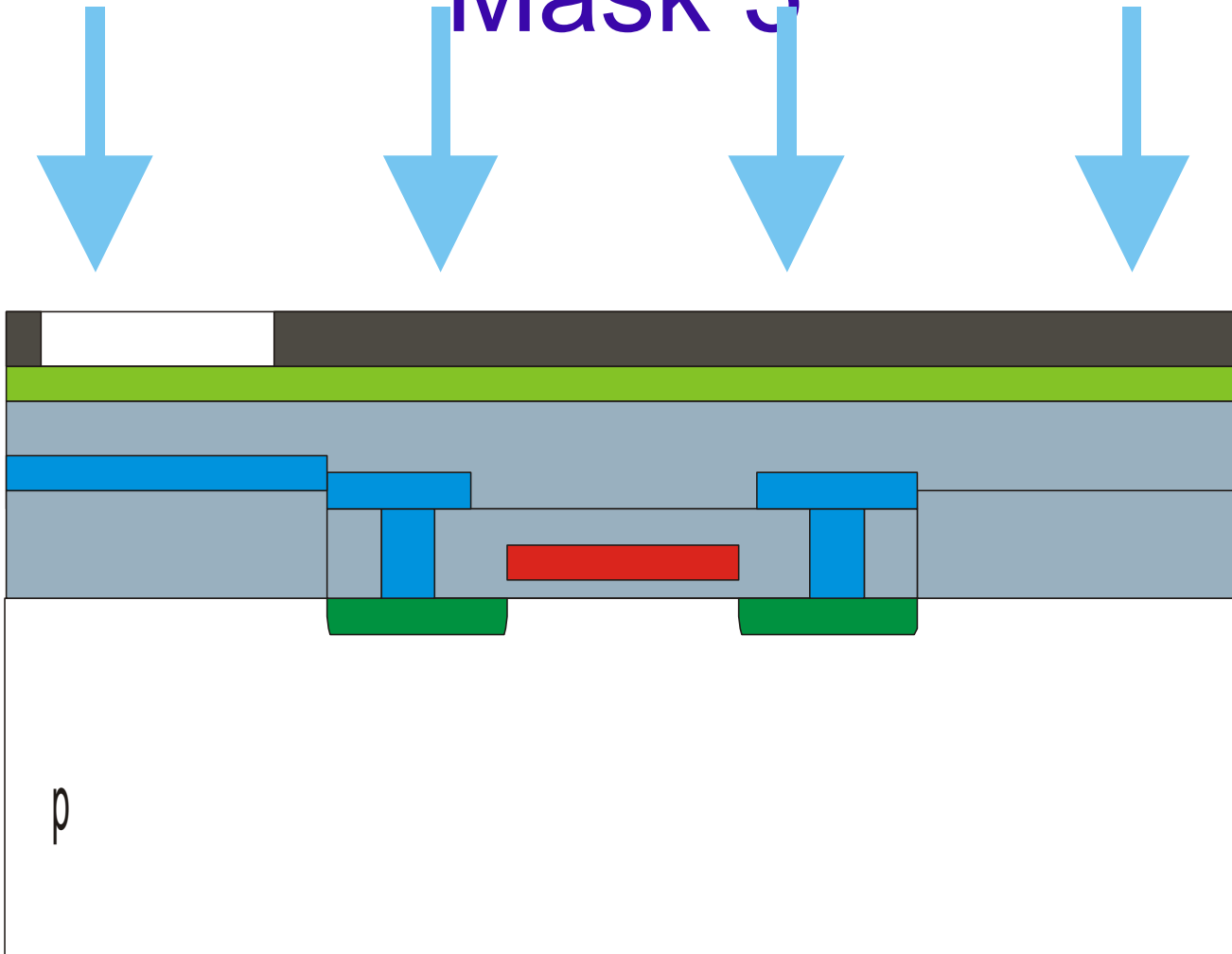
# Deposition of Passivation Layer



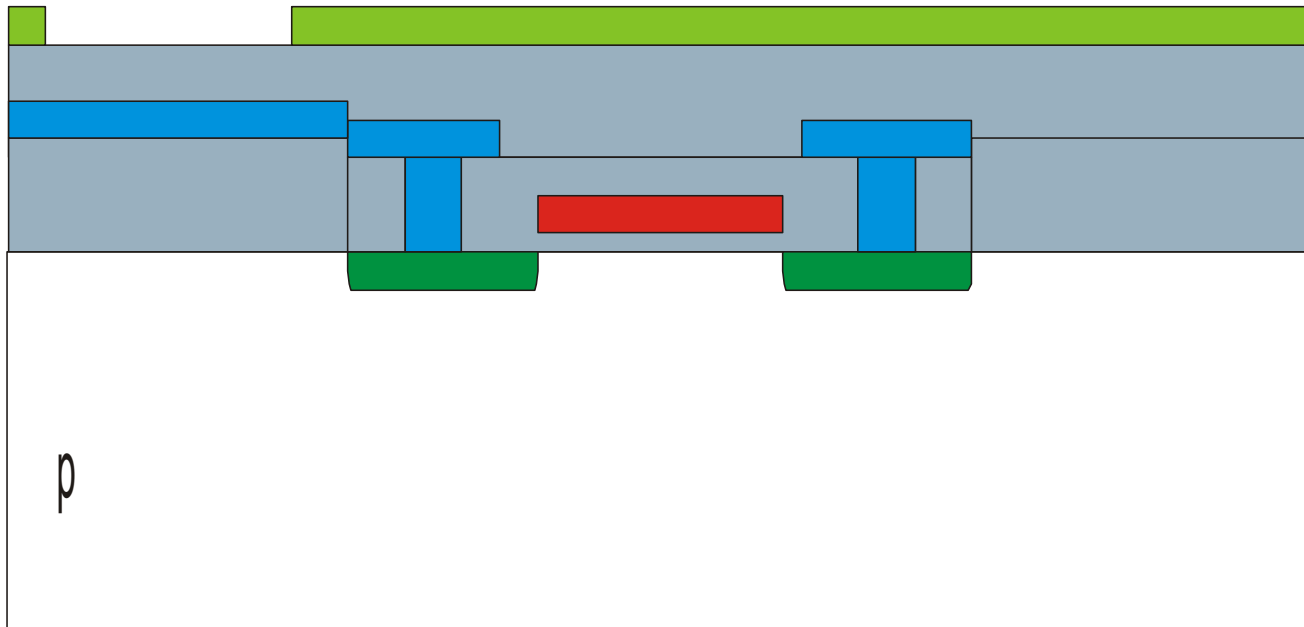
# Deposition of Photoresist



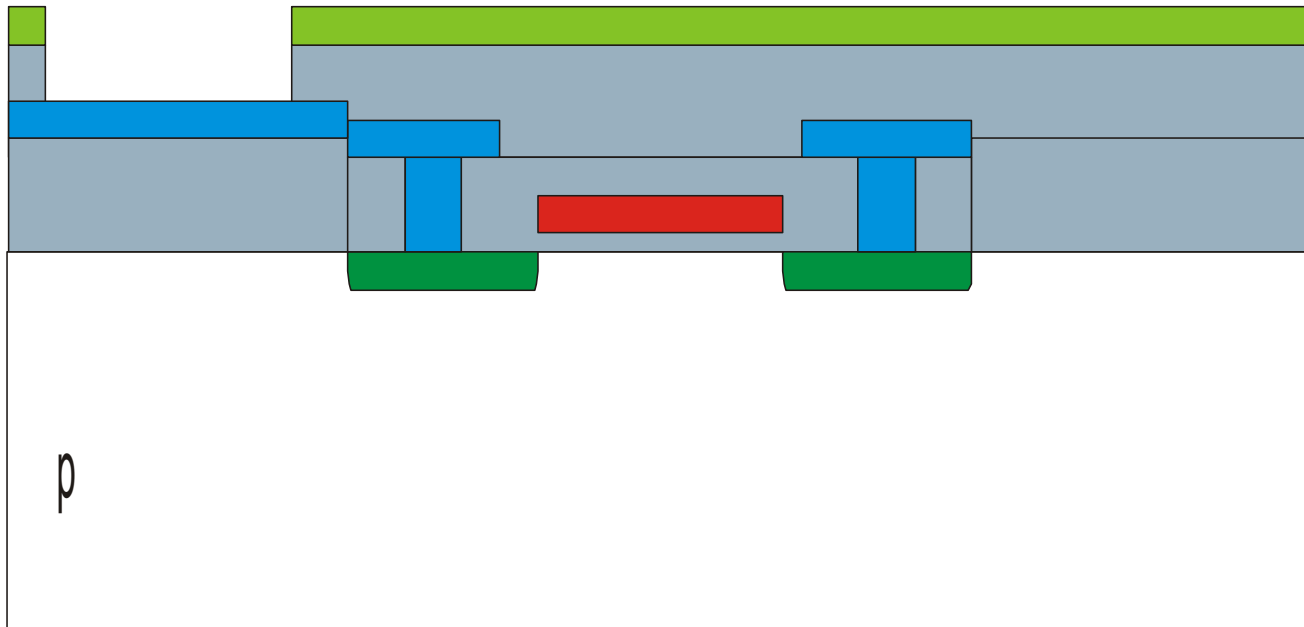
# Mask 5



# Developing of Photoresist



# Oxide Etch





# Removal of Photoresist

